

# Very High Data Rate Optical Wireless Communication with Micro Organic LED

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**Li-Fi  
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Online (Hybrid)**

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# Outline

- 1. Context**
- 2. Design, fabrication and characterisation of high-speed OLEDs**
- 3. Implementation in high-speed transmission**
- 4. On-going ANR DE $\mu$ S project**
- 5. Conclusions & Perspectives**

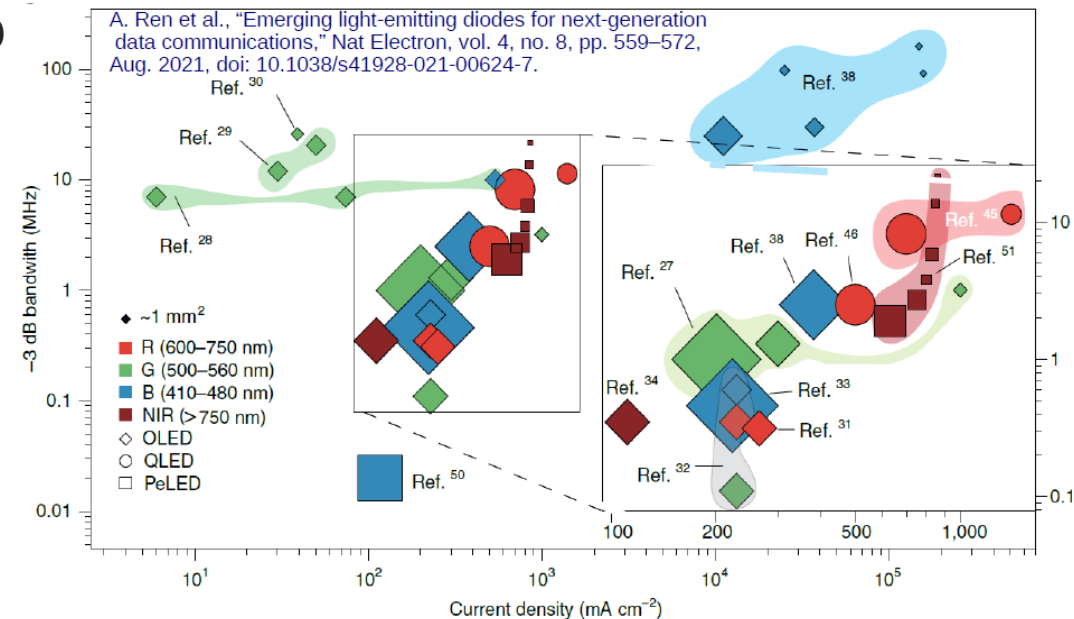
# 1. Context

## ■ Very High-Speed Optical wireless communication with LED

- Recent research on LED-based communications for high speed communications mainly focused on Gallium-Nitride micro-LED devices
- For a long time, organic LED (OLED) were seen as “slow”
- But recently, recent works show that micro-OLED could prove to be as fast as their GaN counterparts

## ■ Organic LED brings several advantages and benefits...

- Lower manufacturing costs and energy needs (30 clean rooms steps)
- Shorter time-to-market
- Lower carbon footprint
- Easier heterogeneous integration on numerous substrates



# 2. Design and fabrication of high-speed OLEDs

## ■ Different substrates for fabrication

- Glass (Bottom emission)
- Silicon (Top emission)

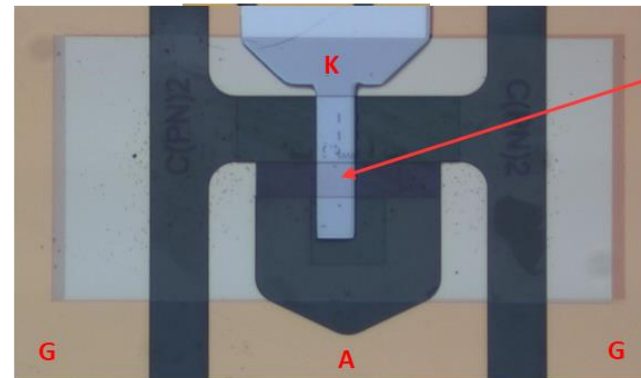
## ■ Fabrication in five phases

- Etching – Structuration of anode, cathode
- Metallisation – Minimize resistive effects
- Resin isolation – Isolate the organic layers
- Thermal vapour deposition – Deposition of organic materials
- Atomic layer deposition – Encapsulation of Al<sub>2</sub>O<sub>3</sub>

## ■ OLED versus High-speed OLED

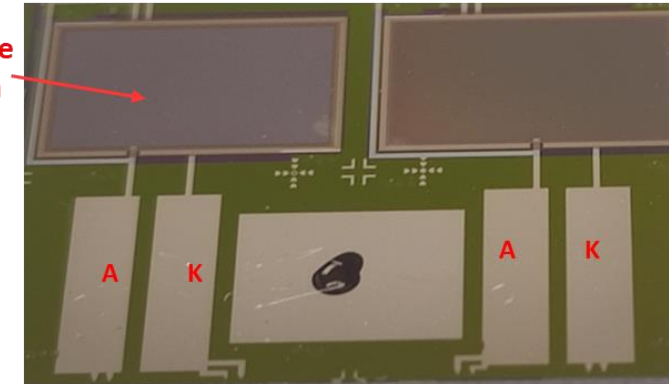
- Small active area (short electrical time constant)
- Coplanar waveguided electrodes
- Short fluorescence lifetime

High speed CPW OLED of 200 μm<sup>2</sup> active area (Glass)



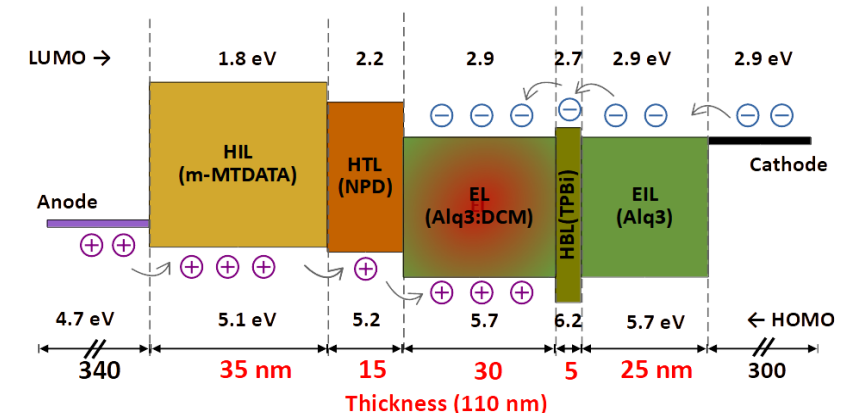
Fabricated at USPN-LPL

OLEDs of 0.44 cm<sup>2</sup> active area (Silicon)



Fabricated at CEA-DOPT

Organic heterostructure of an OLED



# Dynamical OLED model based on small signal analysis

## Organic laser diode rate equations [2]

Variation of Current  $I(t)$

$$\frac{dI(t)}{dt} + \left(1 + \frac{R_d}{R_{S1} + R_{S2} + R_{meas}}\right) \frac{1}{R_d C} I(t) = \frac{1}{R_{S1} + R_{S2} + R_{meas}} \left[ \frac{dV_E(t)}{dt} + \frac{1}{R_d C} V_E(t) \right]$$

Polaron density  $N_p$

$$\frac{d}{dt} N_p = \frac{I(t) P_0}{eAd} - \gamma N_p^2$$

Singlet  $N_S$  and triplet density  $N_T$

$$\frac{d}{dt} N_S(t) = \frac{1}{4} \gamma N_p^2(t) - (\kappa_S + \kappa_{ISC}) N_S(t)$$

$$\frac{d}{dt} N_T(t) = \frac{3}{4} \gamma N_p^2(t) + \kappa_{ISC} N_S(t) - \kappa_T N_T(t)$$

Photon density  $P_{HO}$

$$\frac{d}{dt} P_{HO} = \beta_{sp} \kappa_S N_S - k_{cav} P_{HO}$$

Small signal analysis consideration:  $N_x = N_{x0} + \delta N_x \exp^{j\omega t}$

Transfer function of OLED:

$$\frac{\Delta P_{HO}}{\Delta V} = \left[ \frac{\beta_{sp} \kappa_S \tau_{cav}}{1 + j\omega \tau_{cav}} \right] \times \left[ \frac{1}{2} \frac{\tau_{sp}}{1 + j\omega \tau_{sp}} \right] \times \left[ \frac{1}{2eAd} \times \frac{1}{1 + j\omega \tau_{pi}} \right] \times \left[ \frac{1}{R + R_d} \times \frac{1 + j\omega \tau_{iv2}}{1 + j\omega \tau_{iv1}} \right]$$

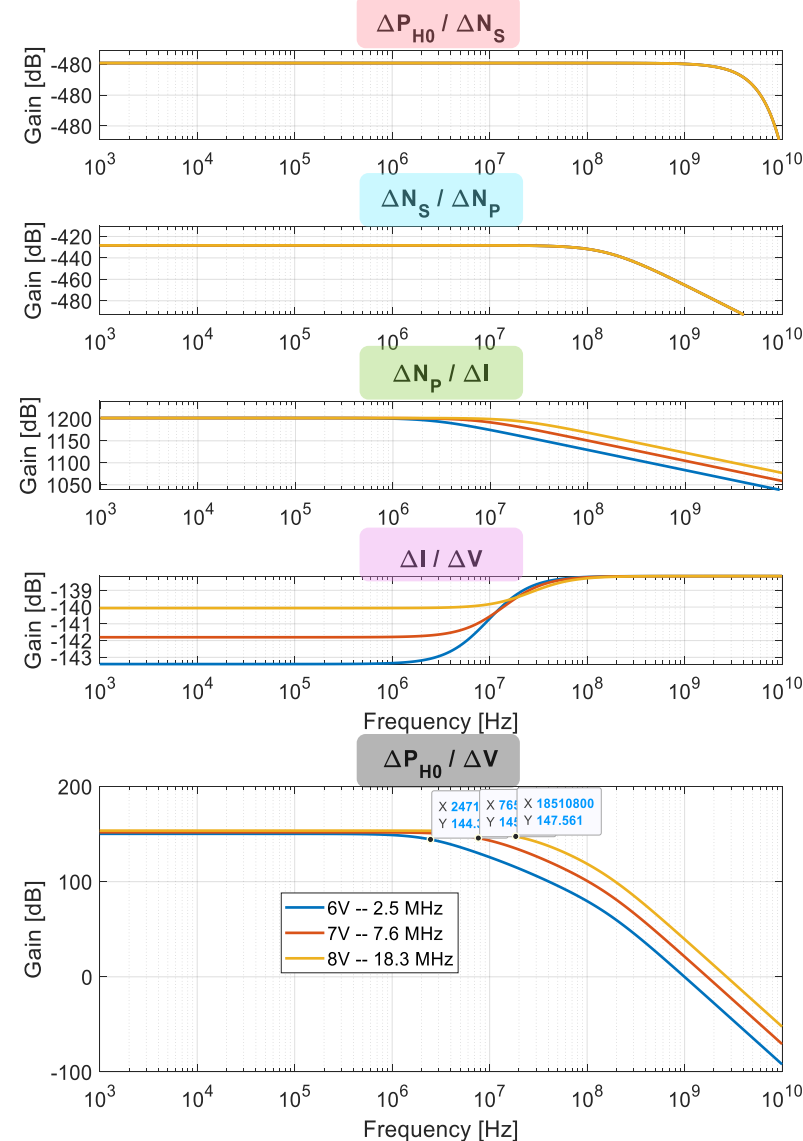
Time constants:

$$\tau_{sp} = \frac{1}{\kappa_S + \kappa_{ISC}}$$

Singlet lifetime  $\kappa_S$

$$\tau_{pi} = \frac{1}{2\gamma \sqrt{\frac{1}{\gamma} \frac{1}{eAd} \frac{1}{R + R_d} V_{E0}}}$$

Bias voltage  $V_{E0}$   
OLED area  $A$   
OLED thickness  $d$

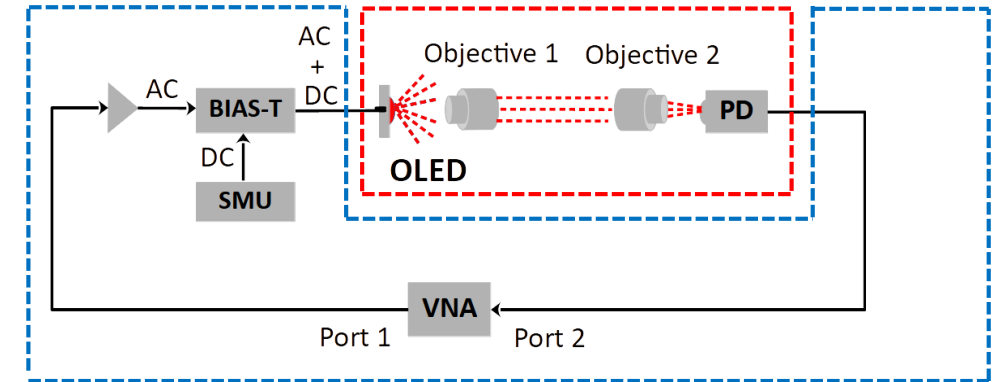


# Optical setups for bandwidth analysis



## ■ Optical section for light collimation onto Photodetector (PD)

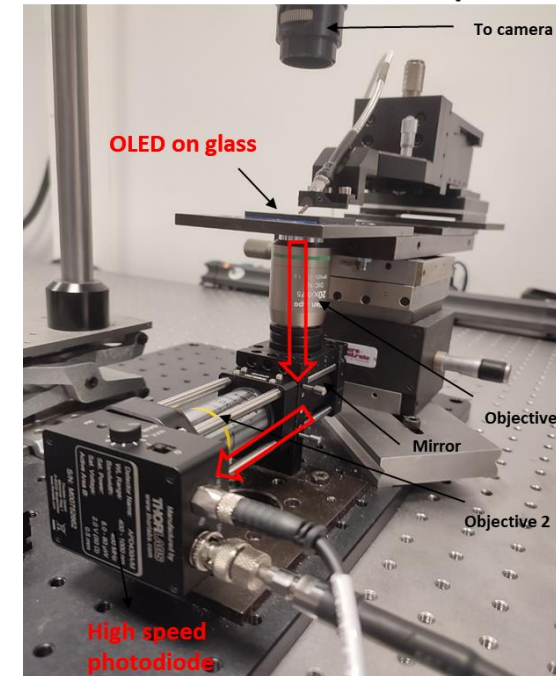
- Maximize the light flux (Numerical aperture)
- Optimize the image size on PD (Magnification)



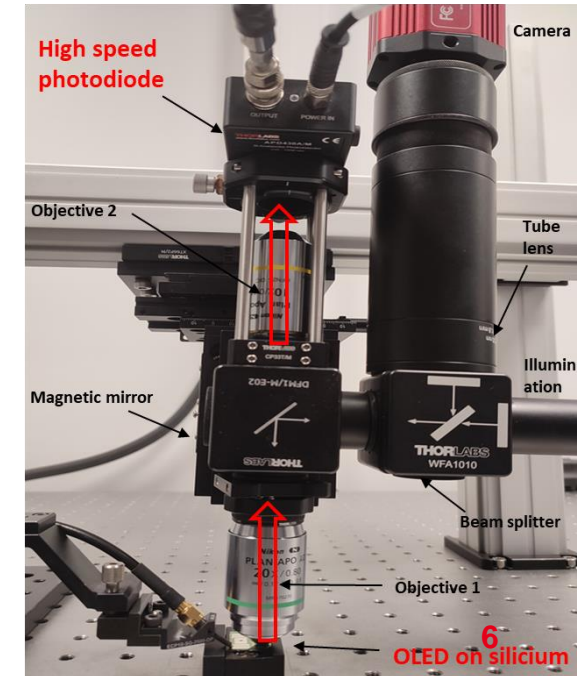
## ■ Electrical section for RIN characterization

- VNA Port 1 → Frequency-sweep RF signal
- Bias-tee for coupling BIAS and RF
- OLED modulation (Electrical-to-Optical)
- High speed photodiode (Optical-to-Electrical)
- VNA Port 2 → Measurement of Rx amplitude and phase

Bottom emission setup



Top emission setup

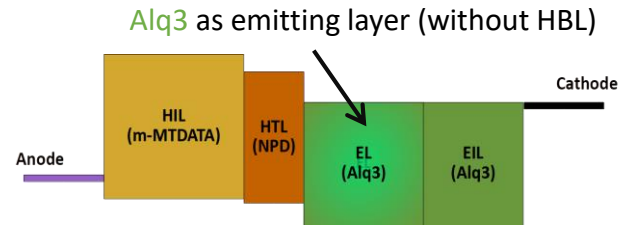
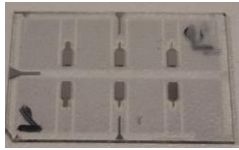


# Heterostructure impact on bandwidth

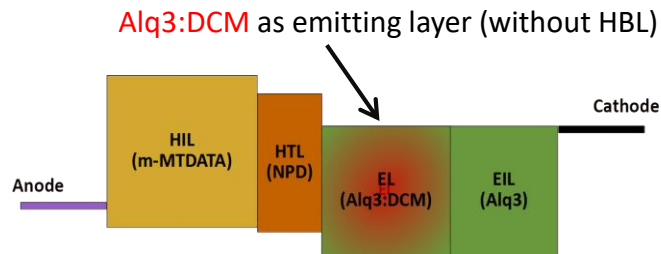


## Effect of the electrodes, emitting layer and hole blocking layer (500 $\mu\text{m}^2$ CPW OLED on glass)

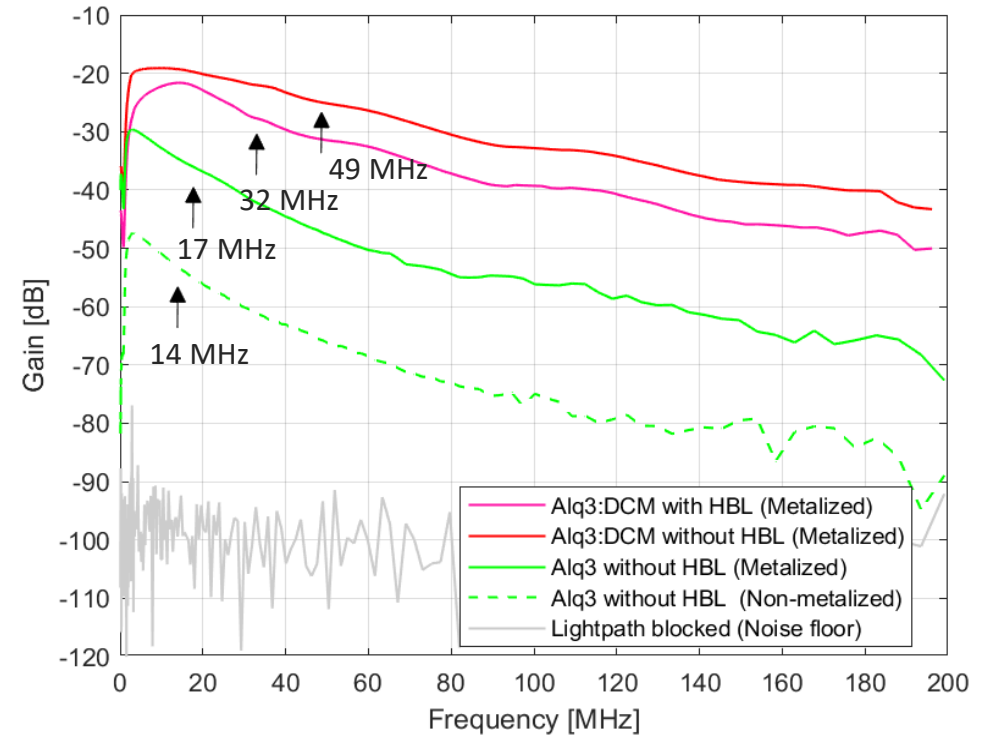
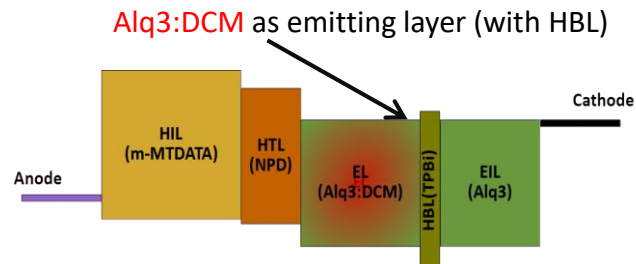
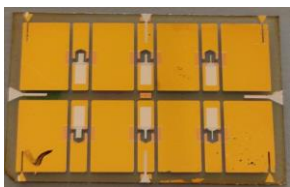
Substrate non-metallized    Substrate metallized



Substrate metallized



Substrate metallized



- Bandwidth increased from 14 MHz to 17 MHz by metallizing the CPW electrodes (RC time constants -  $\tau_{iv1}$ ,  $\tau_{iv2}$ )
- Increased from 17 MHz to 49 MHz by using red emitting layer w/o HBL (Spontaneous emission lifetime  $\tau_{sp}$ )

# Active area impact on bandwidth

## Effect of the OLED active area (500 $\mu\text{m}^2$ , 200 $\mu\text{m}^2$ and 100 $\mu\text{m}^2$ CPW OLED on glass)

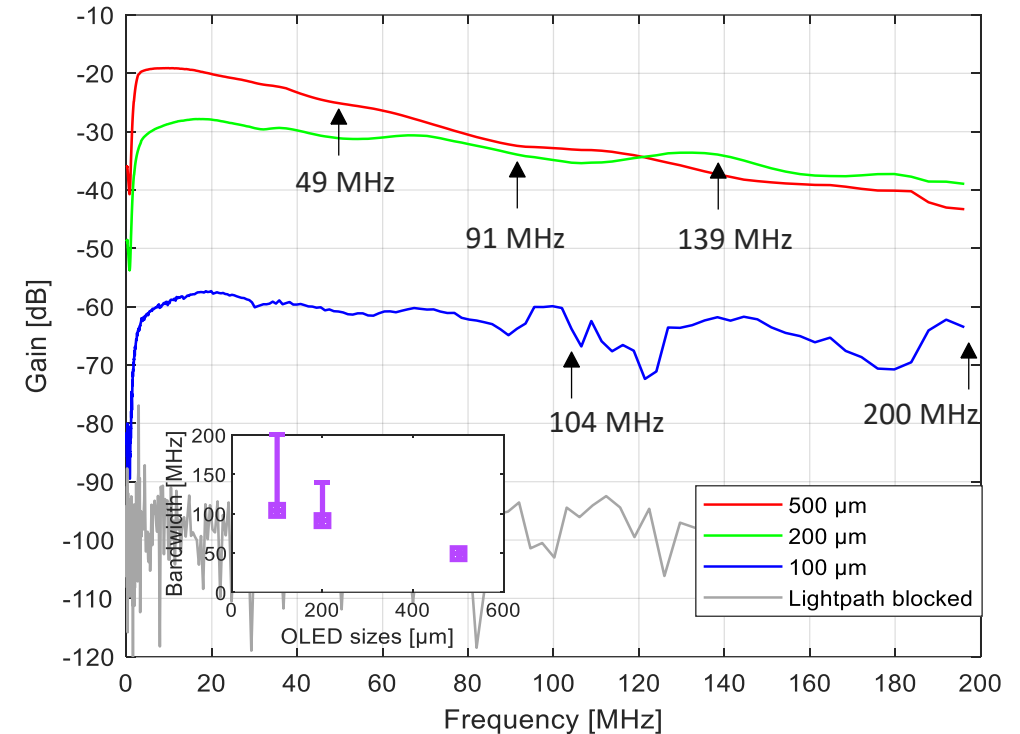
- Electro-to-optical bandwidth relation [3]:

$$f_{3\text{ dB}} = \frac{1}{2\pi C} \left\{ \frac{1}{R_s} + \frac{1}{R_d} \right\}$$

C → Capacitance

R<sub>s</sub> → Serial resistance

R<sub>d</sub> → Dynamic resistance



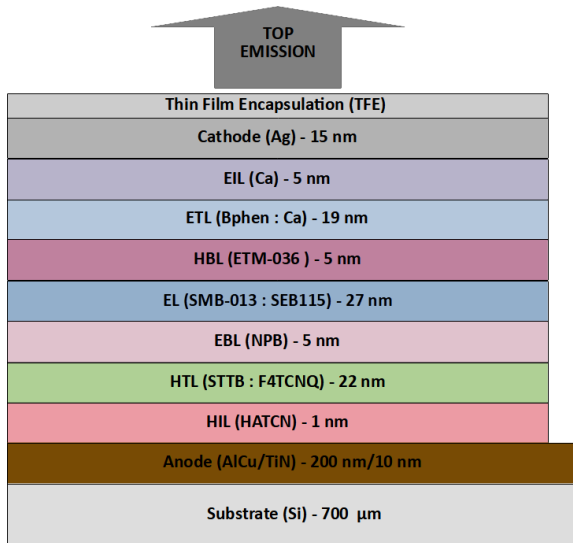
- Bandwidth increased from 49 MHz for 500  $\mu\text{m}^2$  to 91 MHz for 200  $\mu\text{m}^2$  and to >200 MHz for 100  $\mu\text{m}^2$  (Active area)
- Bandwidth at the state of the art → 245 MHz [3]
- Resolution limited by parasitic RF emission



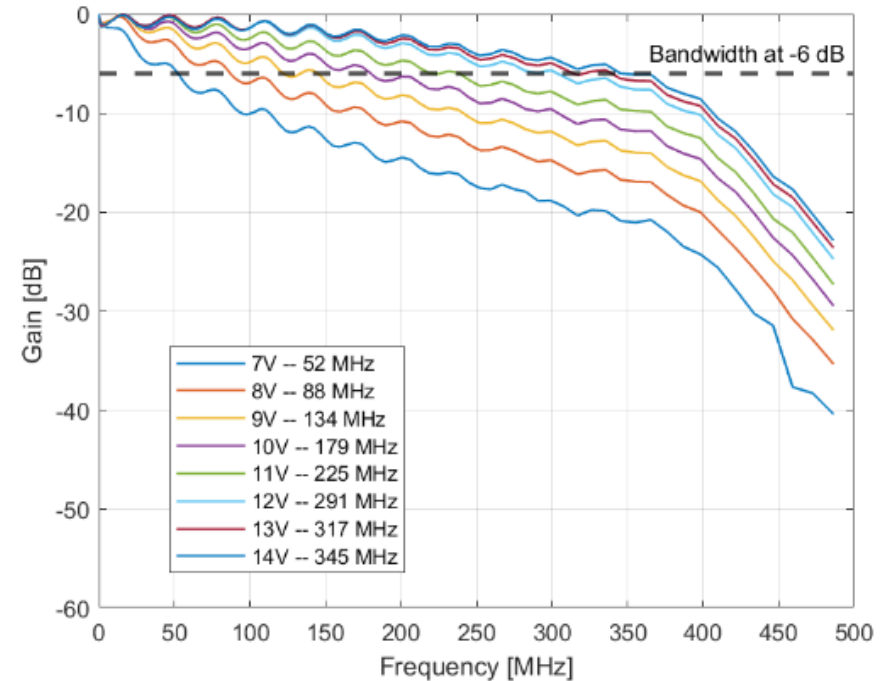
# Bias voltage impact on bandwidth



## Effect of PIN doping on the bias voltage impact (40x40 μm<sup>2</sup> non-CPW OLED on Silicon)



PIN doping in heterostructure



- Langevin recombination rate :

$$\gamma = \frac{e}{\epsilon} (\mu_h + \mu_e) \approx \frac{e}{\epsilon} \mu_0 \exp\left(\frac{-E_a}{kT}\right) \exp\left(\delta \frac{\sqrt{F}}{kT}\right)$$

- Poole Frenkel law :

$$\mu(t) = \mu_0 \exp\left(\frac{\sqrt{V_D(t)}}{V_0}\right)$$

$V_D \rightarrow$  Voltage applied across OLED

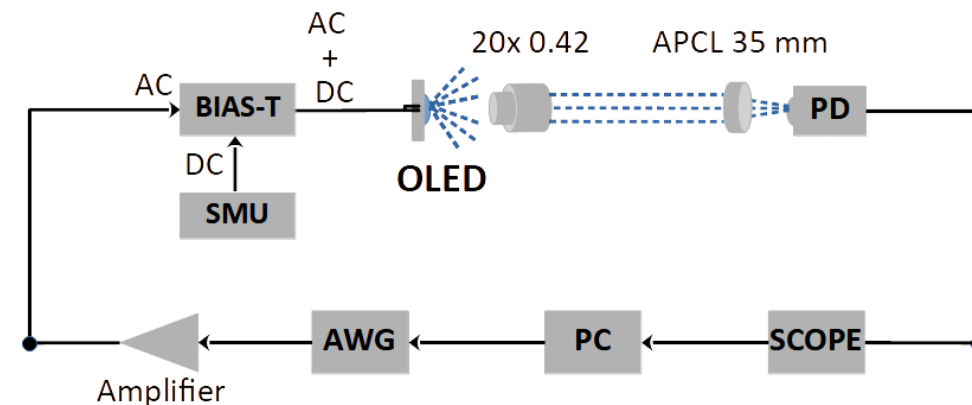
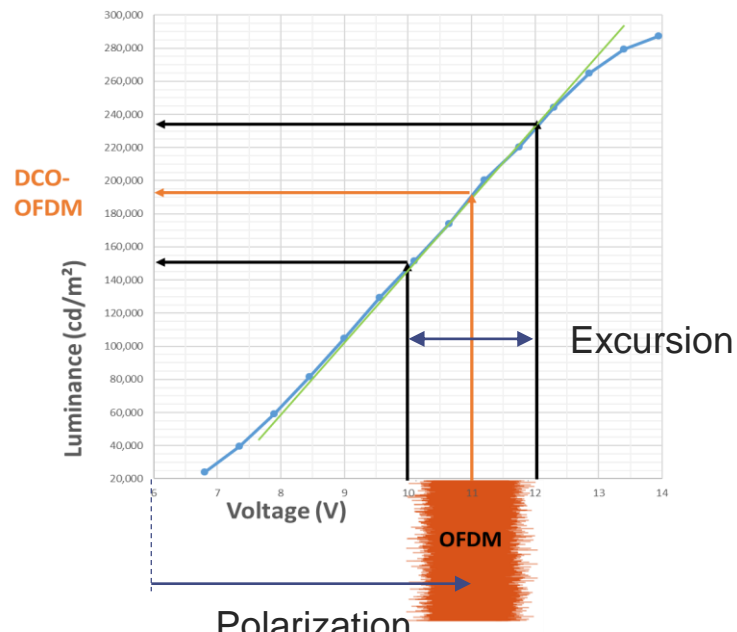
- Bandwidth increased from 52 MHz to 345 MHz when bias voltage is increased
- Bandwidth beyond the state-of-the-art (245 MHz [3])
- Bias voltage increased  $\rightarrow$  Mobility increase exponentially  $\rightarrow$  Bandwidth increase (paper submitted [4])

[3] K. Yoshida et al., "245 MHz bandwidth organic light-emitting diodes used in a gigabit optical wireless data link," Nat Commun, vol. 11, no. 1, Art. no. 1, 2020.

[4] Mohamed Nihal Munshi, Nixson Loganathan, Alexis P.A. Fischer, Luc Maret, Mahmoud Chakaroun, Benoit Racine, "Relative Intensity Noise measurement of high-speed μ-OLEDs towards visible light communication", submitted to Organic electronics.

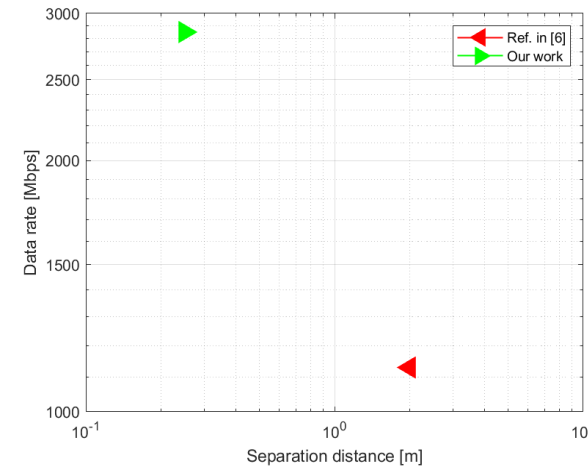
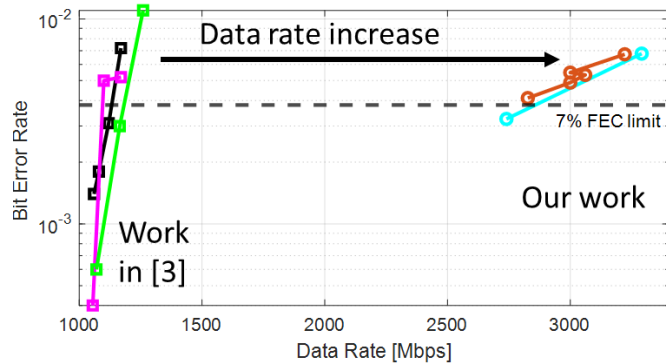
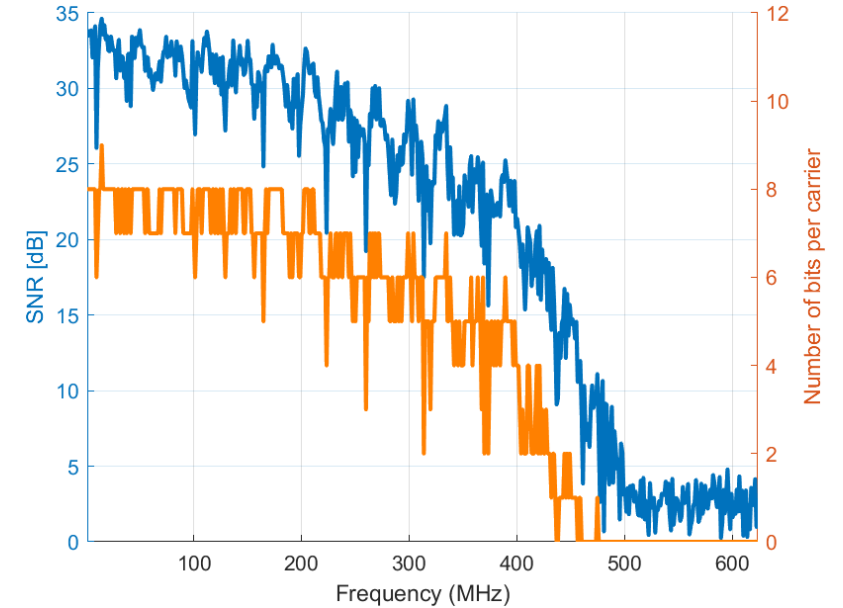
# 3. Implementation in high-speed transmission

- **Using micro-OLED on Silicon:**
  - Primary designed for micro-display
  - Non-CPW electrodes structures
- **Transmission with multi carrier modulation: Direct Current Optical – OFDM (DCO-OFDM)**
  - High spectral efficiency
  - Benefit from high bandwidth using a high DC bias
- **Use of AWG, Amplifier, Scope and PC for transmission**
  - AWG for transmission, Scope for acquisition and PC for pre-processing and post-processing



# Transmission with OLED using DCO-OFDM

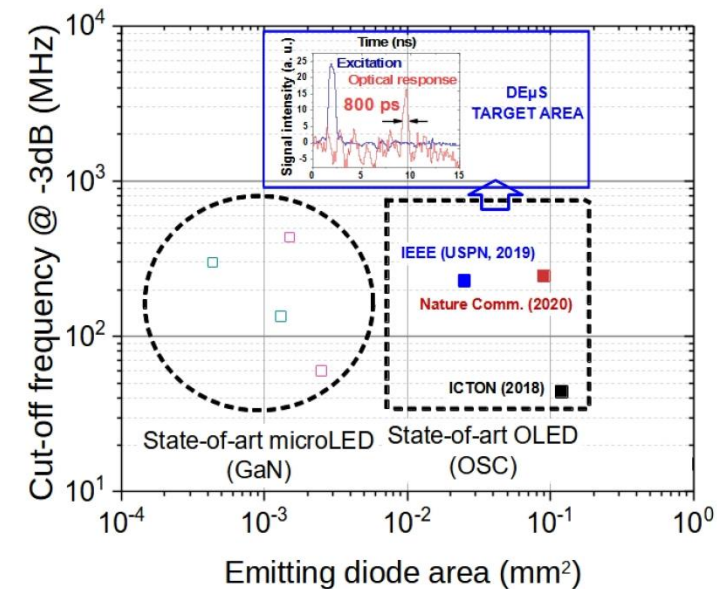
- Best performance reached on a square  $40 \times 40 \mu\text{m}^2$  blue OLED
- Pilot-based transmission for bit and power loading algorithm
  - Modulation bandwidth : DC-500 MHz (Bias  $V_{\text{dc}} = 12 \text{ V}$ )
  - Up to 35dB of SNR
  - Bit loading: up to 9 bits per sub-carrier
- Data rate reached: 2.85 Gb/s at  $\text{BER} = 3.8 \times 10^{-3}$



# 4. ANR DE $\mu$ S project



- French national project between Univ. Sorbonne Paris-Nord and CEA-Leti
- Main objectives:
  - Design of Sub-ns High-Speed Organic Light Emitting Diodes on Silicon
  - Implementation into ultra-high speed communications

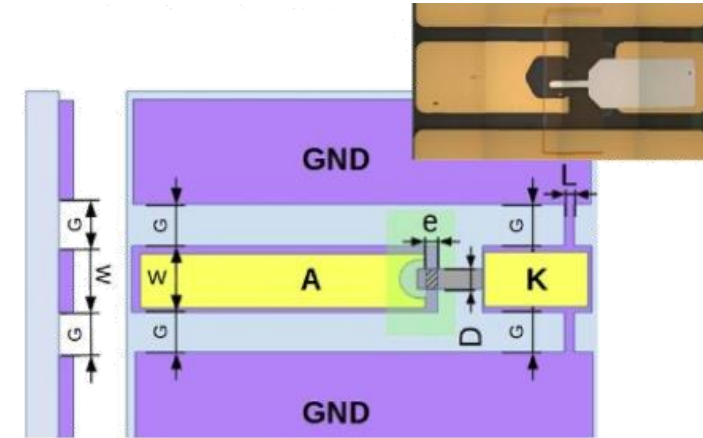


# 4. ANR DE $\mu$ S project



## ■ Research at device level

- Screening of high-speed emitting molecules running in the sub-ns range
- Monolithic integration on silicon
- CoPlanar Waveguided (CPW) electrodes to ensure high-speed electronic response and adapted impedance
- Atomic Layer Deposition (ALD) encapsulation: allows for waveguide coupling



## ■ Innovation at transmission level

- Different single micro-OLED designs for performance analysis
- Fabrication of inline and squared matrices for enhanced system performance:
  - Range increase
  - Integration of DC-less modulations (M-PAM,...) with future integrated CMOS current drives

# Conclusions & Perspectives

## ■ CONCLUSIONS:

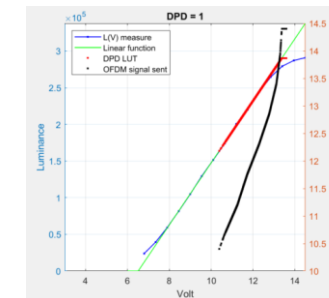
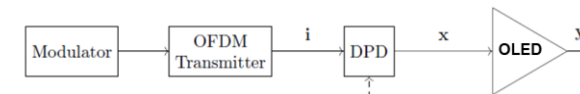
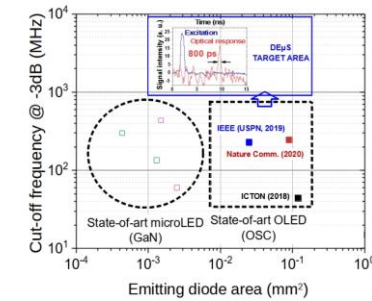
- Fabrication of high speed OLEDs based on a novel technology
- Analysis of heterostructure layer impact on bandwidth
- Analytical model to infer OLED's characteristics
- Bandwidth of 345 MHz and data rate of 2.85 Gb/s
- With further improvements, OLEDs could compete with GaN LEDs

## ■ WORK IN PROGRESS

- Improve transmission performance
  - Linearization of OLED characteristics by Digital Pre-Distortion (DPD)
  - Reduction of Peak to average power ratio (PAPR)
- CPW High Speed OLEDs on silicon (ANR-DE $\mu$ S)
- Transmission on matrices of CPW OLED on Silicon (ANR-DE $\mu$ S)

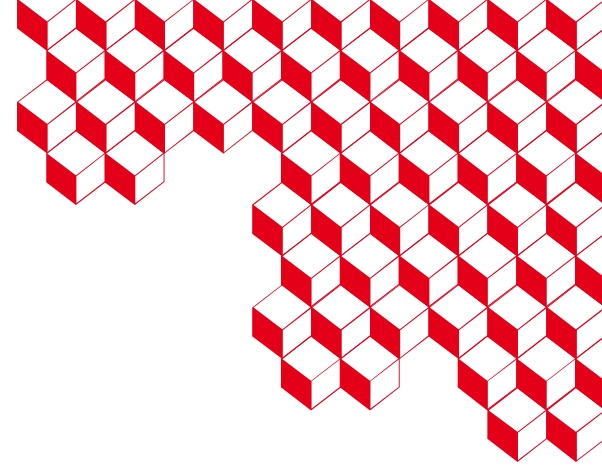
## ■ PERSPECTIVES:

- Targeting bandwidth up to 1 GHz and data rates up to 10 Gb/s
- Going step further into integration:
  - Integrated emitter/receiver optical front-ends
  - Integrated process for optical beamforming
- Positioning  $\mu$ OLED in terms of rate, pJ/bit and Tb/mm<sup>2</sup>





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**THANKS FOR YOUR ATTENTION**

